

**Amendments to the Specification:**

Please amend the Specification as follows:

Please replace paragraph [0001] starting at page 2 of the Specification with the following rewritten paragraph:

[0001] This patent application is related to United States Application No. 09/255,604, filed on February 22, 1999 by Yu, entitled "A Process for Forming Ultra-Shallow Source/Drain Extensions" (now U.S. Patent No. 6,184,097) and is also related to United States Application No. [[\_\_\_\_\_]] 10/440,734, filed on [[\_\_\_\_\_]] May 19, 2003 by Paton, et al., entitled "Disposable Spacer SMOS Process for Forming N-Type Source/Drain Extensions" (~~Atty. Docket No. 39153-641~~), both of which are incorporated herein by reference and assigned to the assignee of the present invention.